Claims

1. A resist transfer pad comprising:

a transfer layer of polydimethylsiloxane; and

a cushion layer attached to the transfer layer and providing flexible support for the transfer layer.

2. The resist transfer pad of claim 1 further comprising a stiffener layer attached to the cushion layer.

3. The resist transfer pad of claim 1 wherein the cushion layer is silicone rubber.

4. A method of applying a photoresist comprising the steps of:

applying a liquid photoresist to transfer pad having a transfer layer of polydimethylsiloxane;

curing the photoresist to form a loaded resist transfer pad ;

pressing the loaded resist transfer pad against a surface of a workpiece; and

peeling the transfer pad off of the surface leaving a coating of photoresist adhering to the surface.

5. The method of claim 4 wherein the workpiece is a slider.

6. The method of claim 5 wherein the transfer pad further comprises a cushion layer attached to the transfer layer of polydimethylsiloxane providing flexible support for the transfer layer.

7. The method of claim 6 wherein the cushion layer is silicone rubber.

8. The method of claim 5 further comprising the step of placing the slider in a pallet prior to the pressing step and wherein the step of pressing further comprises the steps of :

placing the loaded resist transfer pad onto a cover-tape that is larger than the loaded resist transfer pad; and

urging the loaded resist transfer pad and a section of the cover-tape against the slider and the pallet.

9. The method of claim 8 wherein the step of pressing further comprising the step of cutting the cover-tape to allow a section of the cover-tape to move with the slider and the pallet prior to the peeling step.

10. The method of claim 5 wherein the step of pressing further comprises the steps of :

placing the loaded resist transfer pad onto a press plate of a laminator; and

moving the press plate to press the loaded resist transfer pad against the workpiece surface.